



# PROMETH<sub>2</sub>O

---

20IND06 PROMETH2O

## Metrology for trace water in ultra-pure process gases

[www.prometh2o.eu](http://www.prometh2o.eu)

Vito Fericola, INRIM, Italy

Workshop and Training @ Nippon Gases

Torino, 7<sup>th</sup> of March 2024

---

**EMPIR**



**EURAMET**

The EMPIR initiative is co-funded by the European Union's Horizon 2020 research and innovation programme and the EMPIR Participating States



**Semiconductor manufacturing** - demands for UHP process gases with total impurities as low as few ppb.

**Organic electronics** - highly moisture-sensitive, needs ultra-dry manufacture and vapour barrier coatings.

**UHP bulk process gases** - need to be manufactured with total impurities below 1 ppm in volume (grade N6.0 or better).

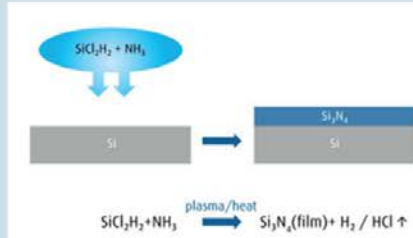
**Instrument manufacturers** - need traceable standards to support their product development while end-users rely on them for instrumental testing and calibration.

Global market for industrial gas reached \$95 billion in 2020. It grew at 5 % per year.

In Europe, in 2020, the gas market reached a value of about € 15 billion.

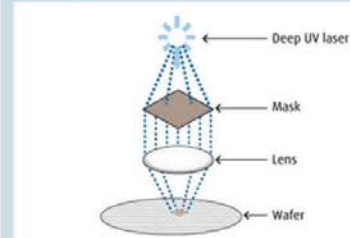
## Processes and Gases Used

### Deposition



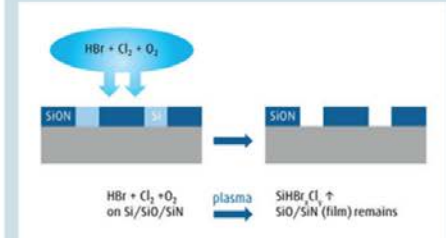
Nitrogen gases:  $\text{NH}_3$ ,  $\text{N}_2\text{O}$   
 Silicon gases:  $\text{SiH}_4$ ,  $\text{Si}_2\text{H}_6$ , TCS, HCDS, TMS  
 Oxygen:  $\text{O}_2$   
 Tungsten hexafluoride:  $\text{WF}_6$   
 Germane:  $\text{GeH}_4$

### Lithography



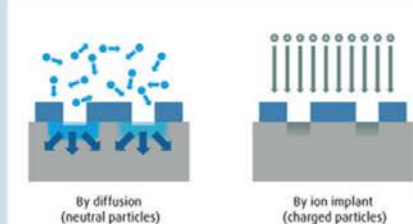
Laser gases: 95+% Ne, with Ar, Kr, and  $\text{F}_2$   
 Carbon dioxide:  $\text{CO}_2$   
 Hydrogen:  $\text{H}_2$

### Etching



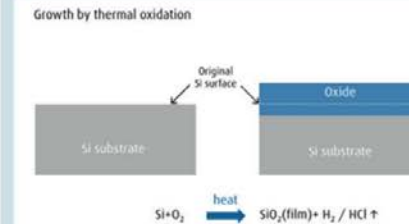
Fluorocarbons:  $\text{C}_2\text{F}_4$ ,  $\text{CF}_4$ ,  $\text{C}_2\text{F}_6$ ,  $\text{C}_3\text{F}_8$ ,  $\text{C}_4\text{F}_8$ ,  $\text{C}_2\text{F}_6$ ,  $\text{C}_2\text{F}_4$ ,  $\text{CHF}_3$ ,  $\text{CH}_2\text{F}_2$ ,  $\text{CH}_3\text{F}$ ,  $\text{C}_2\text{H}_2\text{F}_2$   
 Sulfur hexafluoride:  $\text{SF}_6$   
 Halides:  $\text{HCl}$ ,  $\text{Cl}_2$ ,  $\text{HF}$ ,  $\text{F}_2$ ,  $\text{HBr}$ ,  $\text{ClF}_3$ ,  $\text{XeF}_4$   
 Oxygen:  $\text{O}_2$

### Doping



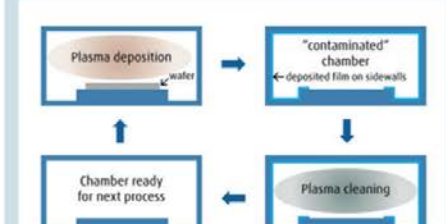
Hydrides:  $\text{AsH}_3$ ,  $\text{BF}_3$ ,  $\text{B}_2\text{H}_6$ ,  $\text{PH}_3$ ,  $\text{GeH}_4$ ,  $\text{Ge}_2\text{H}_6$

### Annealing



Oxygen:  $\text{O}_2$   
 Hydrogen:  $\text{H}_2$   
 Argon: Ar

### Chamber Cleaning



Nitrogen trifluoride:  $\text{NF}_3$   
 Other fluoride gases:  $\text{CF}_4$ ,  $\text{C}_2\text{F}_6$ ,  $\text{C}_4\text{F}_8$ ,  $\text{ClF}_3$ ,  $\text{SF}_6$   
 Chloride gases:  $\text{HCl}$ ,  $\text{Cl}_2$   
 Fluorine:  $\text{F}_2$

[https://www.linde-gas.com/en/images/Gasworld%20-%20Creating%20a%20Semiconductor%20FEB18\\_tcm17-477345.pdf](https://www.linde-gas.com/en/images/Gasworld%20-%20Creating%20a%20Semiconductor%20FEB18_tcm17-477345.pdf)

gasworld • February 2018

gasworld.com/specialty-gas-zone

## Creating a semiconductor and the gases that make it happen

By Dr. Paul Stockman, Head of Market Development, Linde Electronics



**Water vapour is the single largest matrix contaminant** in ultra-high purity (UHP) process gases used in key technology areas.

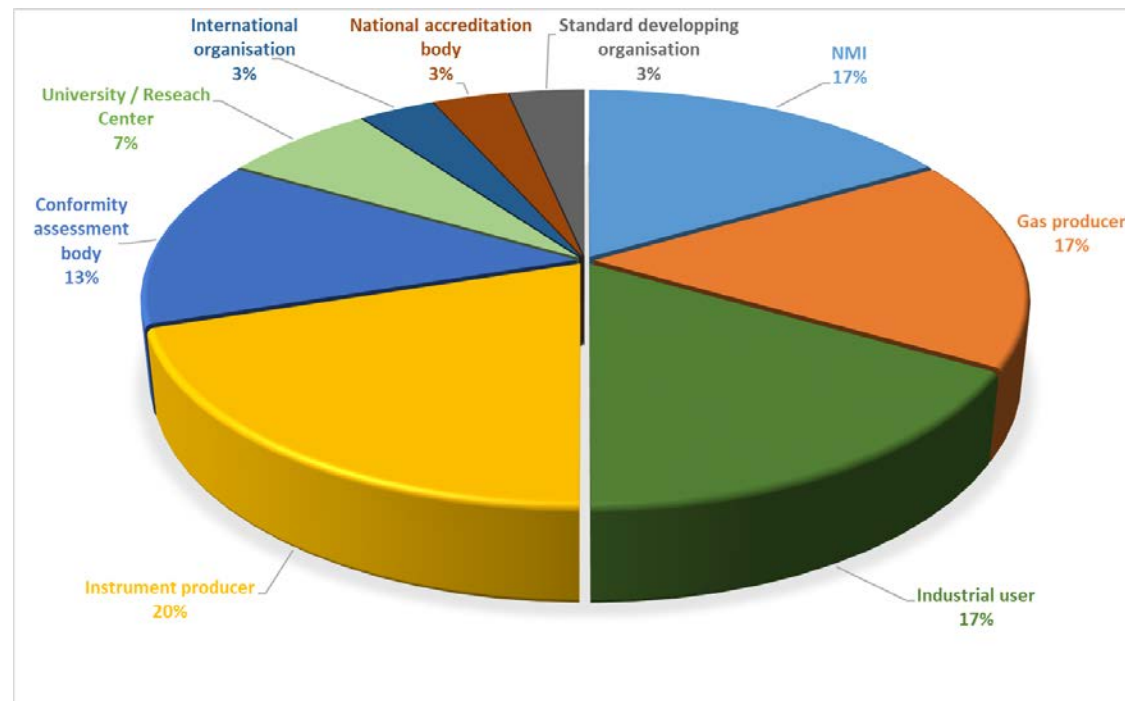
Its measurement presents **great challenges to both gas manufacturers and analytical instrument makers.**

The project is aiming at:

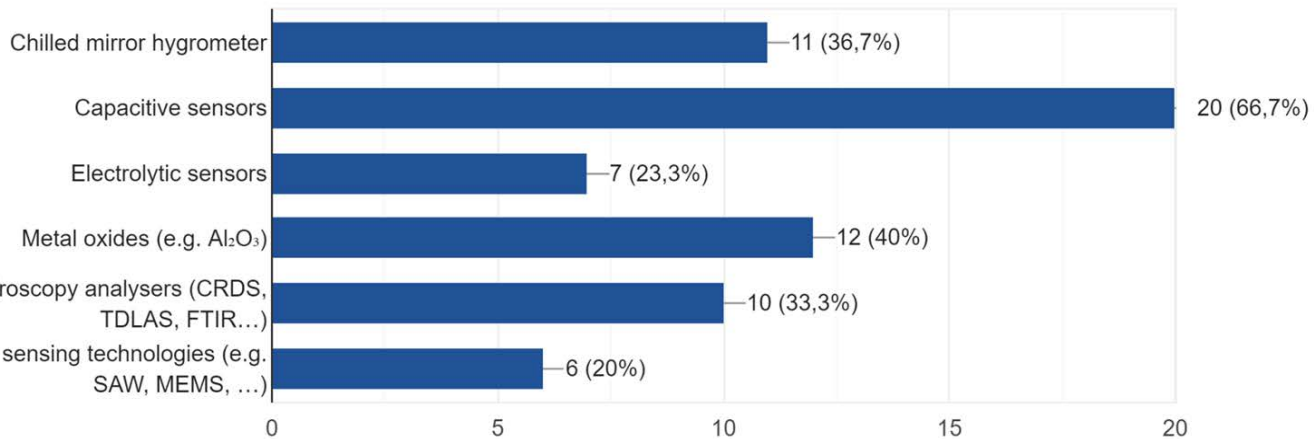
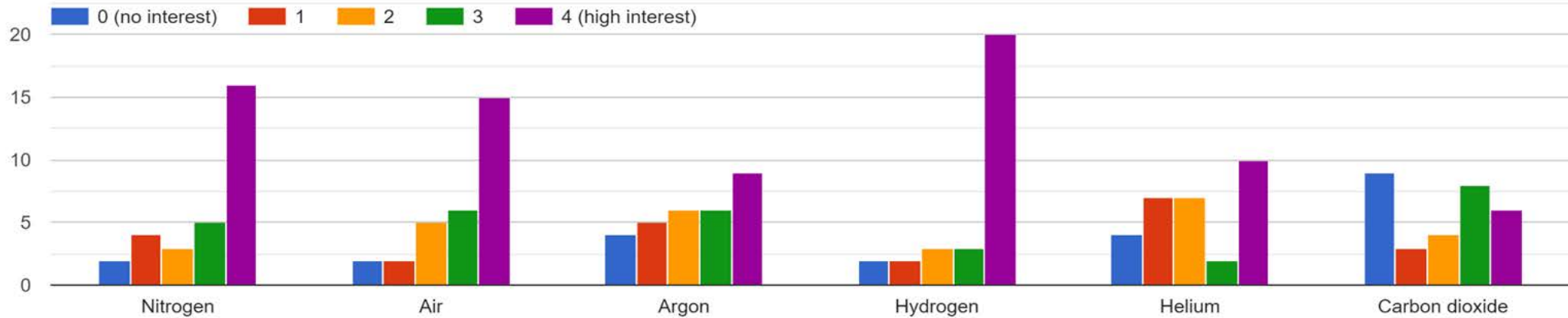
- **filling the gap** between the demand of traceable measurements and the available humidity standards currently limited at  $\sim 1 \mu\text{mol/mol}$ .
- **developing traceable and improved methods** for trace water measurement relevant to the production and use of UHP gases.
- **facilitating the uptake of the technology** by the gas industry supply chain through exploiting knowledge and services developed in an European-wide metrology infrastructure.



## Surveying stakeholders needs and priorities



Steering Board made of 21 key stakeholders among gas producers, instrument manufacturers, and international scientific organisations.

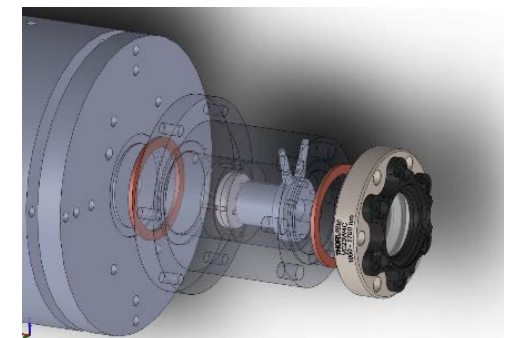
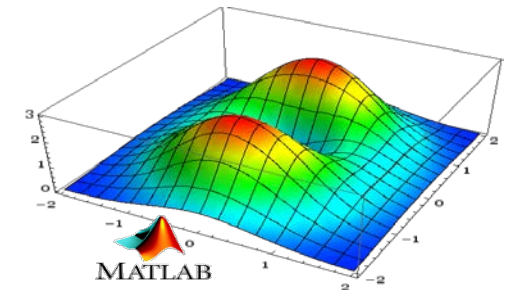


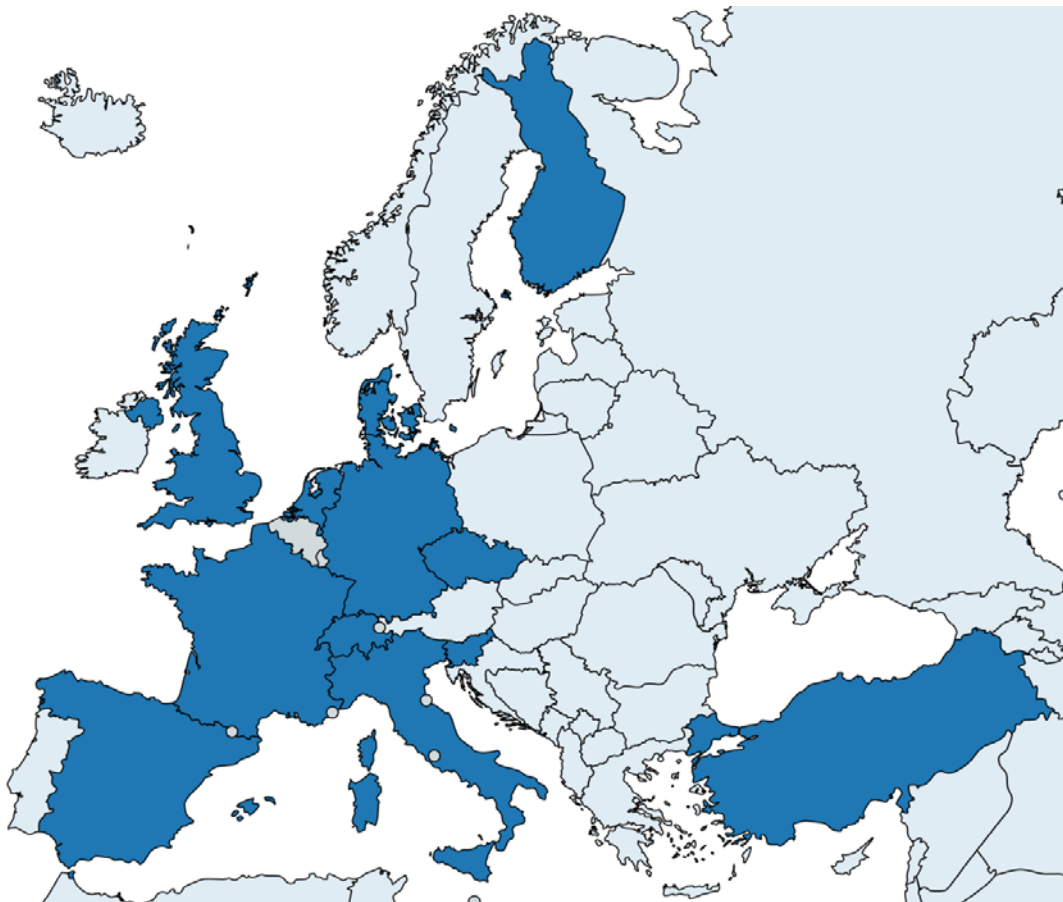
*"I need to measure the trace water content in pure process gases as part of the quality assurance process."*

*"We focus on hydrogen production by water electrolysis and fuel cell applications."*

*"We need an international traceable system for calibration at under 0.1 ppm."*

- **New primary standards** for trace water vapour in N<sub>2</sub>, Ar and H<sub>2</sub> down to 5 nmol/mol (or -105 °C frost point temperature) at pressures up to 1 MPa.
- **New/improved measurement methods** in the amount fraction range between 5 μmol/mol and 5 nmol/mol (*rel. uncertainty 3 % to 8 %*).
- **New data and correlation equations** of water vapour enhancement in N<sub>2</sub>, Ar and H<sub>2</sub> in the temperature range from -30 °C to -90 °C and pressures up to 1 MPa.
- **Demonstration at industrial facilities** with real-time measurements and on-site calibrations.
- **Toolkits of metrological solutions** for robust measurement traceability in the production of UHP process gases.





19 partners from 12 countries → 240 person-months



## Stakeholder's Steering Board

Robust traceability by suitable primary standards

Improved trace water measurement methods

Improved knowledge of real humid gas mixtures

Creating impact



Demonstration at two industrial sites  
Facilitation of end-user uptake

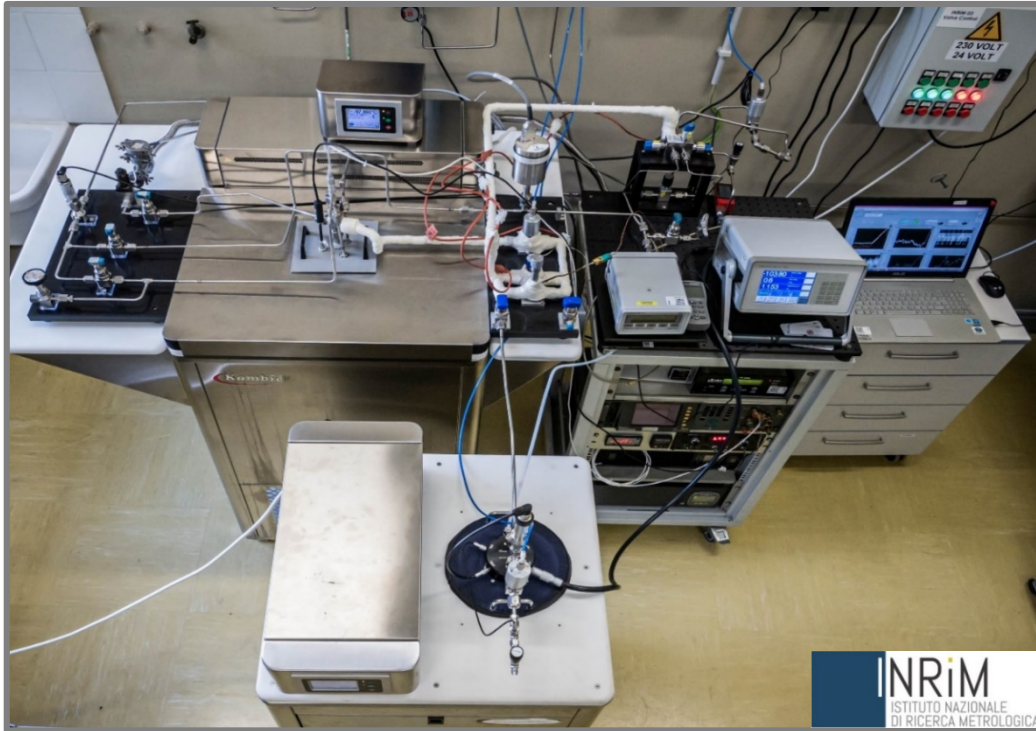


## ❖ Development and improvement of primary humidity standards

- Trace water in Ar and N<sub>2</sub> from 5 ppm down to 5 ppb (Rel. uncertainty: 3 % to 8 %)
- Frost point temperature from -65 °C down to -105 °C (Std. uncertainty: 0.35 °C at -105 °C)
- Operating pressure up to 1 MPa

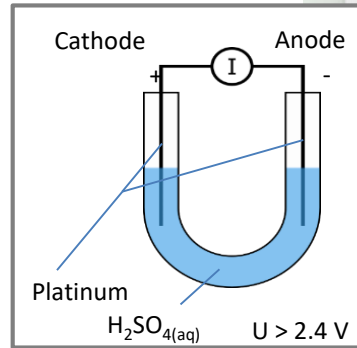
## ❖ 6x systems

- Three thermodynamic saturation-based frost point generators;
- A Coulometric trace water generator;
- A permeation system based on a magnetic suspension balance;
- A dilution-based (two-flow) humidity generator.



## LFP primary humidity generator - Mark 2

- Frost-point temperature: -105 °C to -20 °C
- Water vapour mole fraction: 5 ppb to 1000 ppm
- Pressure: 200 hPa to 0.68 MPa (N<sub>2</sub> and Ar)



 PTB  
Physikalisch-Technische Bundesanstalt  
Nationales Metrologieinstitut

## Coulometric Trace Water Generator (CTWG)

- Amount fraction > 5 ppb
- Rel. uncertainty: 8 %



 VSL

## Permeation system based on a passivated MSB

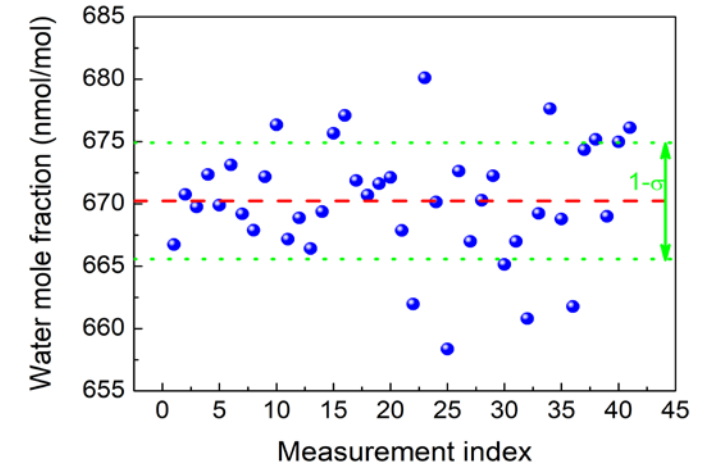
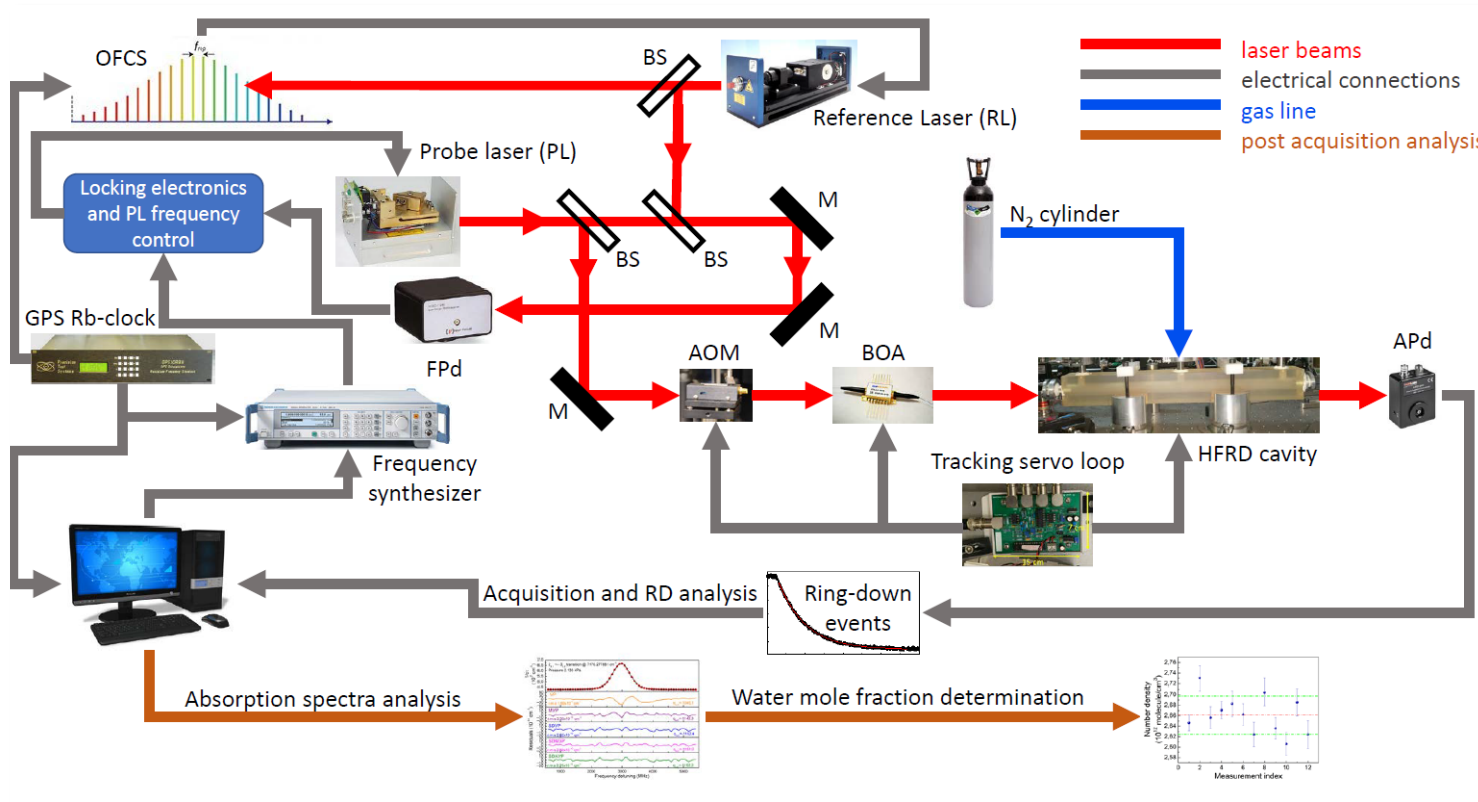
- Range: 50 ppb to 5 ppm

## ❖ Development and improvement of optical analysers

- Target: H<sub>2</sub>O traces in Ar, N<sub>2</sub>, H<sub>2</sub> [from 5 ppm (-65 °C) to 5 ppb (-105 °C) @ 0.1 MPa].
- Relative uncertainty: 3 % (at 5 ppm) to 8 % (at 5 ppb)

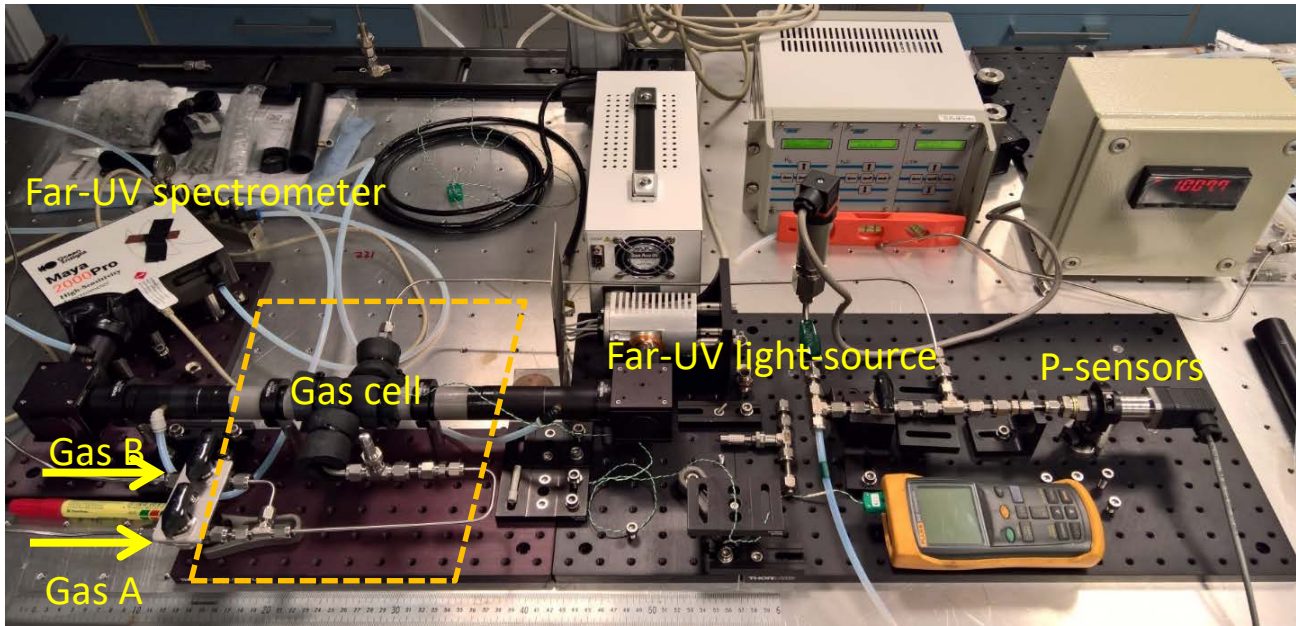
## ❖ 4x systems

- NIR comb-calibrated frequency-stabilized cavity ring down spectrometer (CC-FS-CRDS);
- NIR cavity-enhanced frequency modulated (CE-FM) spectroscopy hygrometer development;
- Far-UV absorption spectroscopy system development;
- Upgrade of existing high-resolution FTIR system.



$$x_w = (671 \pm 4) \text{ nmol/mol}$$

Contribution (k=1)	Type A (%)	Type B (%)
Statistical	0.5	
Line strength		0.3
Frequency scale		Negl.
Line shape model (SDVP)		0.1
RD per point & frequency step		< 0.2
Laser scan width		< 0.2
Gas temperature		0.05
Partition function		0.04
Pressure		0.05
<b>Overall combined uncertainty = 0.7 %</b>		

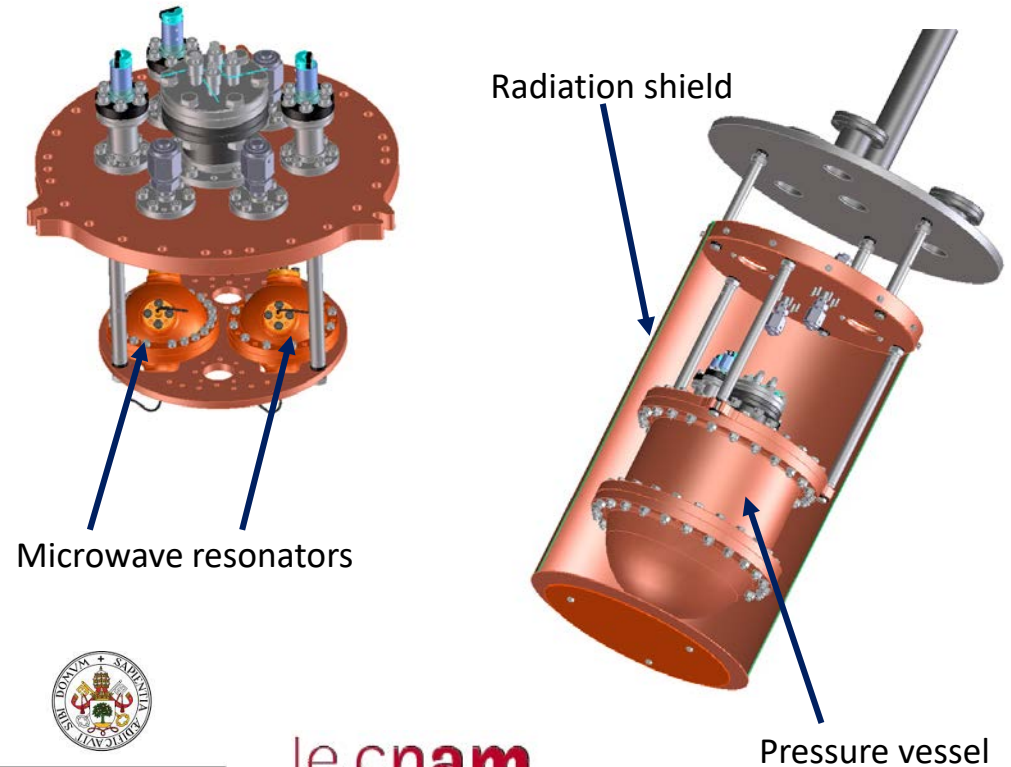


## Far-UV spectroscopy system

- highly-modular gas cells: (0.5 to 100) cm;
- flow or static measurement: (0 to 100) bar;
- 100-cm cell with DURSAN® coatings;
- two-way spectra analysis: “full” and “DOAS”



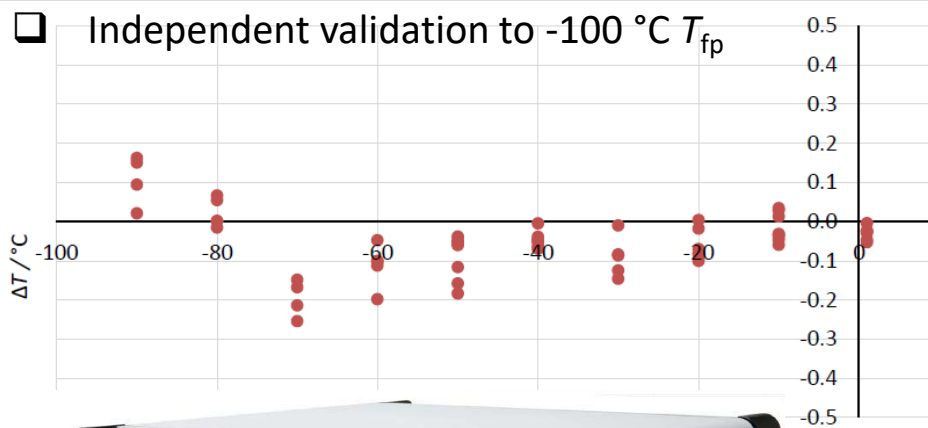
## Microwave-based trace water hygrometers to measure the enhancement factor of H<sub>2</sub>O vapour in N<sub>2</sub>, Ar, and H<sub>2</sub>



Universidad de Valladolid

le cnam

## Accelerated development and validation of a portable frost point generator (FPG)



**VAISALA**  
**Qrometric**  
 Industrial and scientific metrology



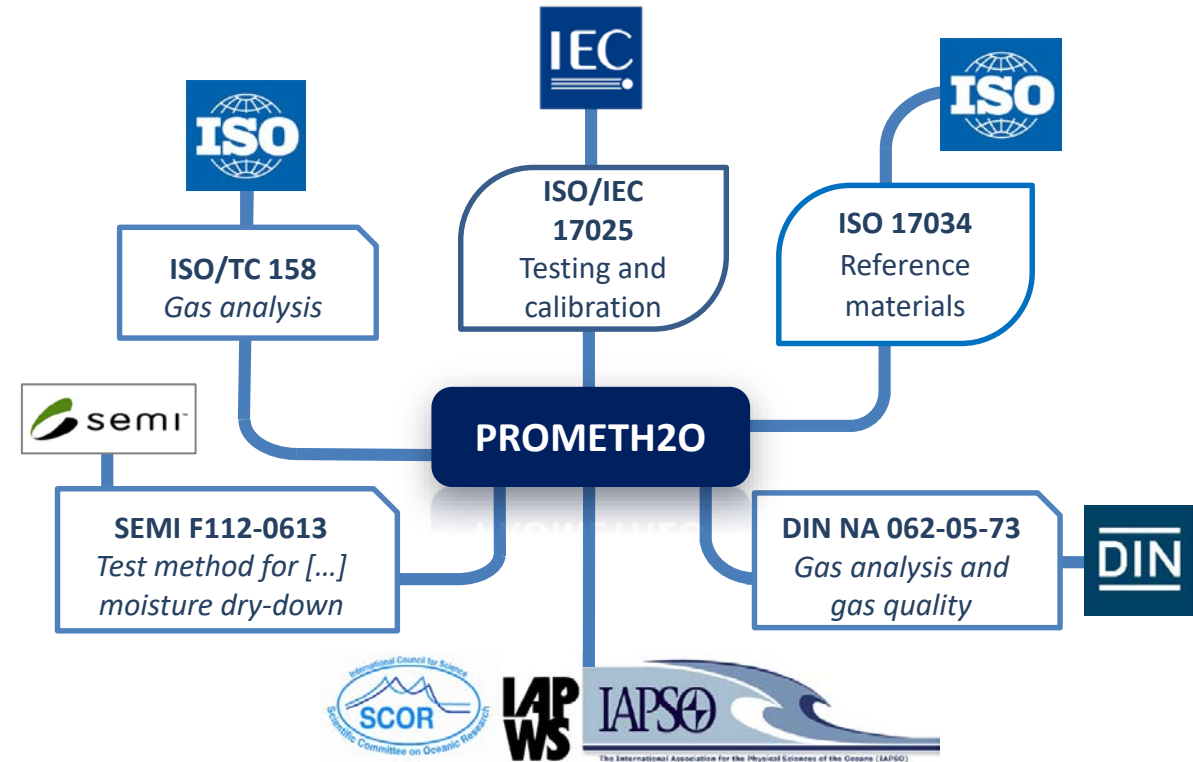
Traceable assessment of state-of-the-art commercial hygrometers down to  $-105\text{ }^{\circ}\text{C}$  (5 ppb)



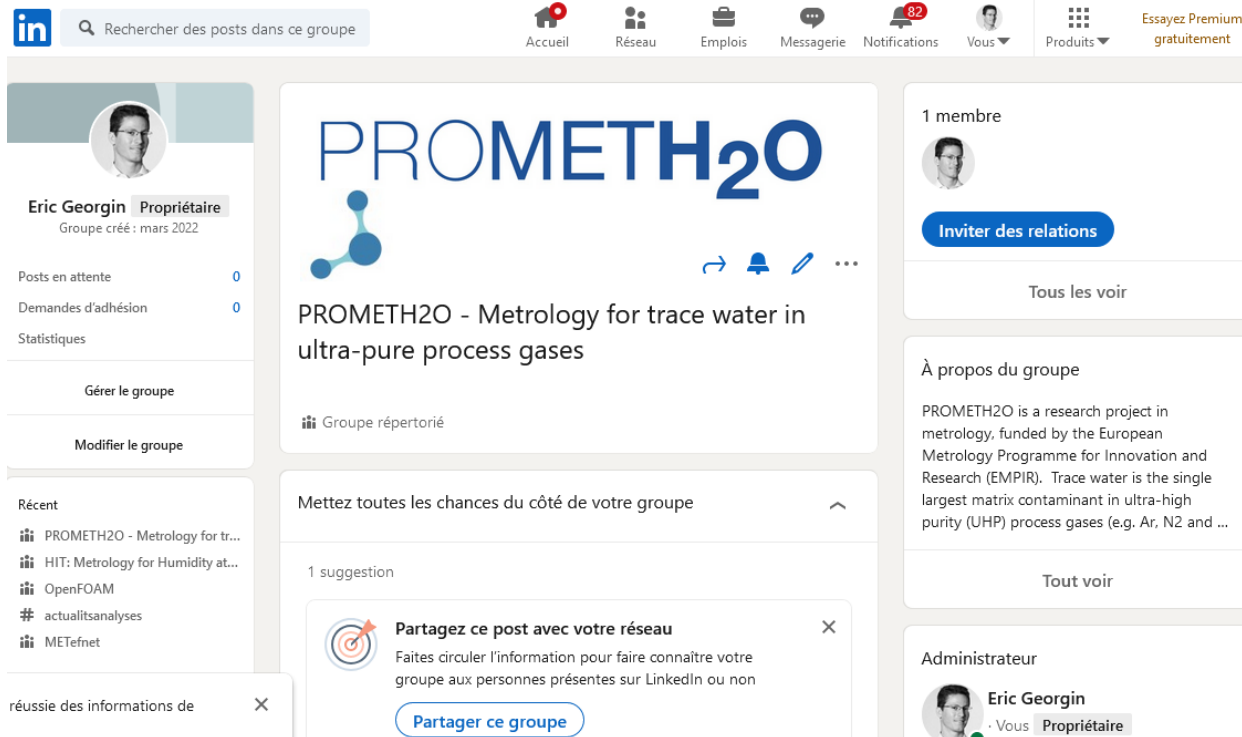
**NIPPON GASES**

Test bed demonstrators  
 Industrial production facility of speciality gases that includes pure and UHP gases and humid gas mixtures.

- ❑ Availability of **primary standards** and **transfer standards** to provide traceability, also via calibration services, to trace water analysers.
- ❑ **Measurement range:** 5 µmol/mol to 5 nmol/mol, or equivalently -65 °C to -105 °C frost point.
- ❑ **Documented and validated software tools** to estimate the enhancement of water vapour in N<sub>2</sub> and Ar and its uncertainty in the range between -30 °C and -90 °C and pressure up to 1 MPa.
- ❑ **Early impact on UHP gas manufacturing:** on-site traceable calibration of water contamination at industrially-relevant facilities.
- ❑ **Establishment of an European-wide measurement infrastructure.**

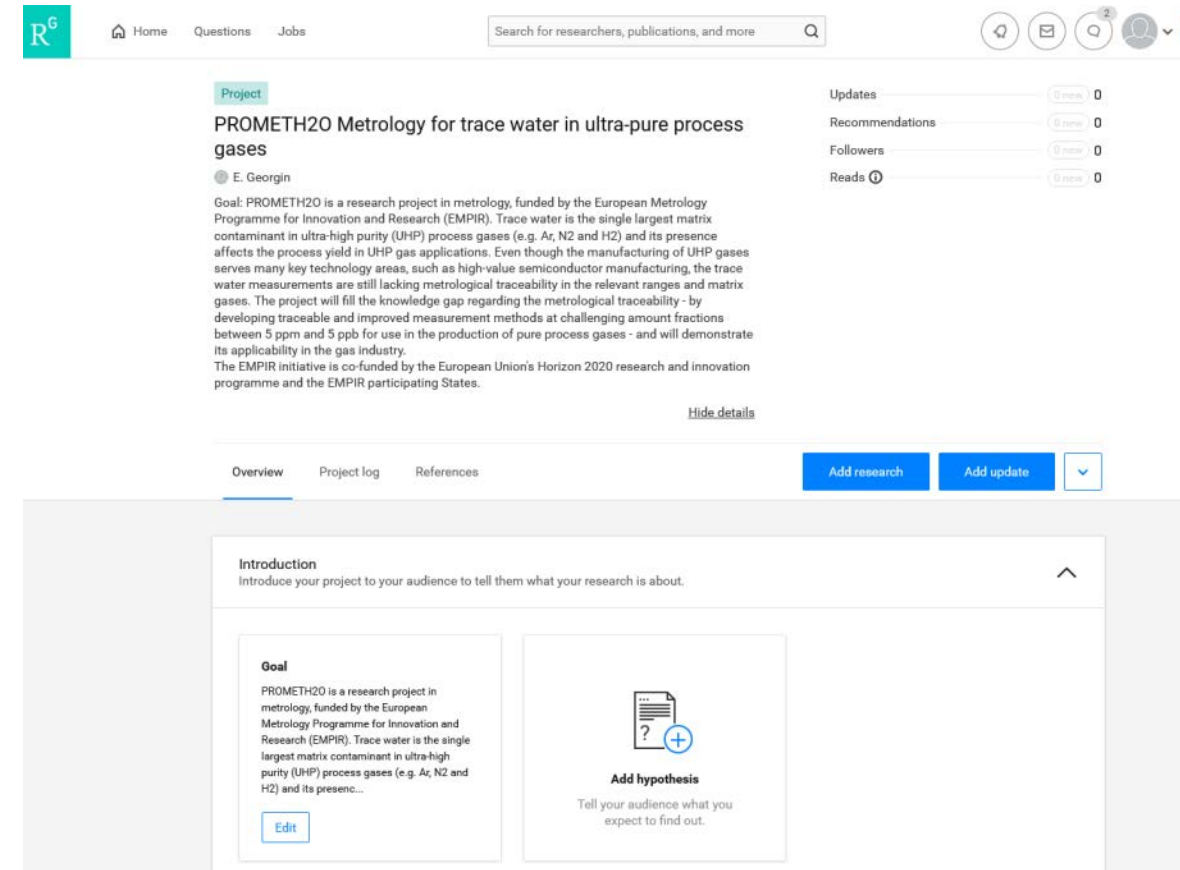


## LinkedIn



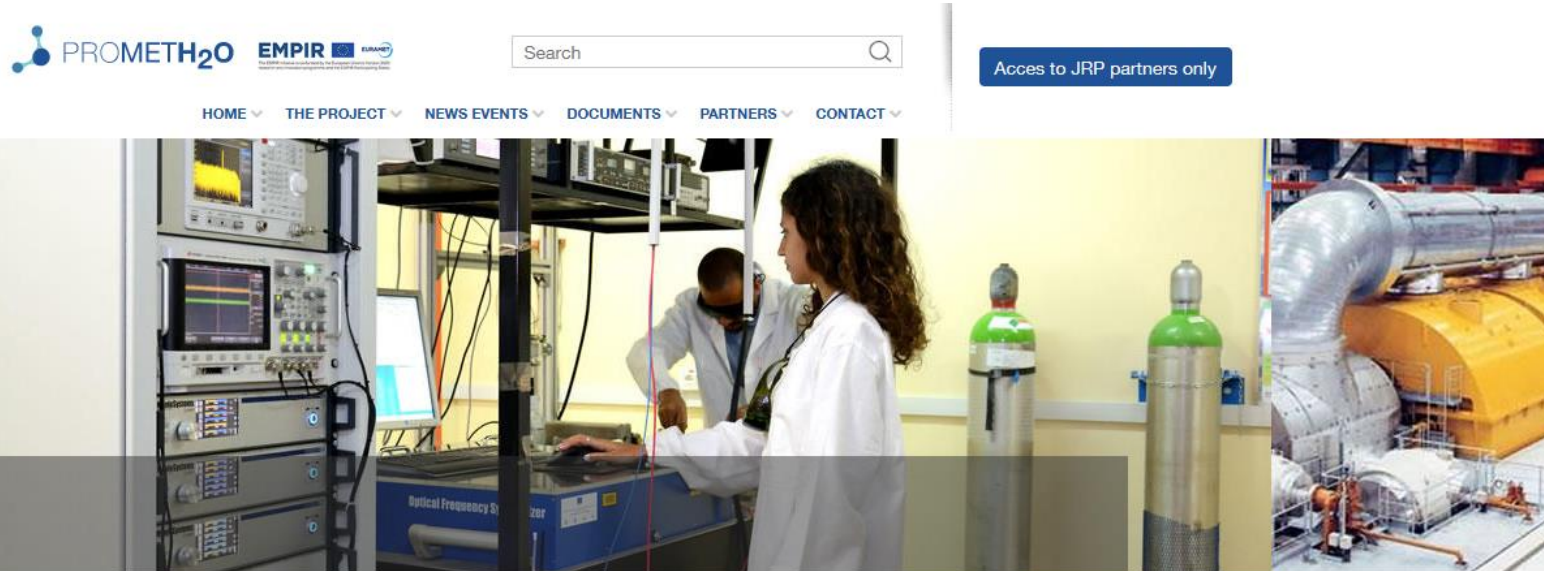
The screenshot shows the LinkedIn profile of the 'PROMETH2O - Metrology for trace water in ultra-pure process gases' group. The group is owned by Eric Geogin and was created in March 2022. It currently has one member. The group description states: 'PROMETH2O is a research project in metrology, funded by the European Metrology Programme for Innovation and Research (EMPIR). Trace water is the single largest matrix contaminant in ultra-high purity (UHP) process gases (e.g. Ar, N2 and H2) and its presence affects the process yield in UHP gas applications. Even though the manufacturing of UHP gases serves many key technology areas, such as high-value semiconductor manufacturing, the trace water measurements are still lacking metrological traceability in the relevant ranges and matrix gases. The project will fill the knowledge gap regarding the metrological traceability - by developing traceable and improved measurement methods at challenging amount fractions between 5 ppm and 5 ppb for use in the production of pure process gases - and will demonstrate its applicability in the gas industry. The EMPIR initiative is co-funded by the European Union's Horizon 2020 research and innovation programme and the EMPIR participating States.'

## Research gate



The screenshot shows the ResearchGate project page for 'PROMETH2O Metrology for trace water in ultra-pure process gases' by E. Geogin. The project description is: 'Goal: PROMETH2O is a research project in metrology, funded by the European Metrology Programme for Innovation and Research (EMPIR). Trace water is the single largest matrix contaminant in ultra-high purity (UHP) process gases (e.g. Ar, N2 and H2) and its presence affects the process yield in UHP gas applications. Even though the manufacturing of UHP gases serves many key technology areas, such as high-value semiconductor manufacturing, the trace water measurements are still lacking metrological traceability in the relevant ranges and matrix gases. The project will fill the knowledge gap regarding the metrological traceability - by developing traceable and improved measurement methods at challenging amount fractions between 5 ppm and 5 ppb for use in the production of pure process gases - and will demonstrate its applicability in the gas industry. The EMPIR initiative is co-funded by the European Union's Horizon 2020 research and innovation programme and the EMPIR participating States.'

[www.prometh2o.eu](http://www.prometh2o.eu)



## THE PROJECT

*Metrology for trace water in ultra-pure process gases*

### Overview

Trace water is the single largest matrix contaminant in ultra-high purity (UHP) process gases. Even though the manufacturing of UHP gases serves many of the key technology areas, such as high-value semiconductor manufacturing, trace water measurements are still lacking measurement traceability in the relevant ranges and matrix gases.

[READ MORE →](#)

*Thank you for your attention!*